

IN THE SPECIFICATION

Please amend the paragraph beginning at page 3, line 18, as follows:

To cope with such problems, a method has been proposed by which α crystal structure alumina films can be formed while still lowering the substrate temperature. For example, it is reported by O. Zywitzki, G. Hoetzschi et al. that when reactive sputtering (pulsed magnetron sputtering) is carried out using a pulsed high output power source (11-17 kW), aluminum oxide films with the corundum structure (α crystal structure) are formed even at 750° C (cf Surf. Coat. Technol. 86-87, 1996, pp. 640-647).